

IN THE SPECIFICATION:

Please amend paragraph [0045] to read:

-- The less the plasma density utilized at the provided deposition surfaces, relative to the maximum plasma density in migrating around beam axes A, the more homogeneous, i.e. equally distributed, becomes the plasma density distribution. But that simultaneously at only approximately 20% of the plasma density utilization nevertheless very high deposition rates of at least 400 nm/min at temperatures of maximally 500°C can be attained, is surprising. --